

to-roll moving disposable web consisting essentially of a polymeric material and wherein said substrates are held to said web by friction against or electrostatic attraction to a web surface;

(b) a central processing chamber which is maintained under vacuum and through which at least a portion of said continuously moving web travels;

(c) at least one deposition device which is located within said central processing chamber, where at least a portion of said continuously moving web is exposed to material deposited from said deposition device;

(d) a first moving platform which moves in an x direction and a y direction, which transfers a substrate onto said continuously moving web; and

(e) a second moving platform which moves in an x direction and a y direction, which transfers a substrate from said continuously moving web.

4. (Once Amended) The apparatus of Claim 1, wherein at least one deposition device is a sputtering device.

5. (Once Amended) The apparatus of Claim 1, wherein a device is present which permits web splicing during continuous operation of said apparatus.

7. (Once Amended) The apparatus of Claim 1, wherein said polymeric material is PET.

8. *The apparatus of Claim 4, wherein a power applied to a cathode in said sputtering device is RF power.*

9. *The apparatus of Claim 8, wherein said cathode is a sputtering target.*

10. *The apparatus of Claim 9, wherein a sputtering target used in said sputtering device is rectangular in shape.*
11. *The apparatus of Claim 9, wherein said sputtering target is comprised of a ceramic or metal.*
12. (Once Amended) The apparatus of Claim 11, wherein said sputtering target is comprised of a material having optical transmission properties useful in optical applications.
13. *The apparatus of Claim 4, wherein said sputtering target sputtering device includes a planar magnetron.*
14. (Once Amended) The apparatus of Claim 1, wherein at least one isolating shield is used to separate one thin film deposition area from another thin film deposition area.
15. (Once Amended) The apparatus of Claim 1, wherein at least said first or said second moving platform is located within a plenum chamber which is at a pressure which is different from the pressure in said central processing chamber.
16. (Once Amended) The apparatus of Claim 1, wherein said central processing chamber is maintained at a base vacuum of at least 10^{-5} Torr (1.3×10^{-3} Pa).
17. (Once Amended) The apparatus of Claim 1, wherein said apparatus also includes a cooling surface which permits the cooling of said continuously moving disposable web within said central processing chamber.

19. (Once Amended) A method for depositing at least one thin film on a substrate useful in electronic applications, the method comprising the steps of :
- placing a series of substrates onto an in-line continuously moving disposable web consisting essentially of a polymeric material, wherein said substrates are held to said web by friction against or electrostatic attraction to said web surface;
 - exposing a surface of said moving disposable web on which said substrates are sitting to at least one depositing material, to form at least one layer of material on a substrate; and,
 - unloading said substrate from said continuously moving disposable web.
20. (Once Amended) The method of Claim 19, wherein said depositing material is deposited using physical vapor deposition.
21. (Once Amended) The method of Claim 20, wherein a pressure at said surface of said substrate is about 10^{-5} Torr (1.3×10^{-3} Pa) or a lower pressure.
22. (Once Amended) The method of Claim 20, wherein said sputtering is carried out using a planar magnetron, and wherein an RF power is applied to a sputtering target, which RF power is about 100 to about 5,000 W at a frequency of about 10 to about 30 MHz.
23. (Once Amended) The method of Claim 19, wherein a plurality of layers is deposited, wherein said moving disposable web is a roll-to-roll web, and wherein the roll speed is based on a film thickness of a depositing material layer which has a narrow processing window relative to other depositing material layers.
25. (Once Amended) The method of Claim 19, wherein said substrate is a plastic substrate.